



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION OF

PRIL et al.

Appln. No.: 09/899,566

Filed: July 6, 2001

Confirmation No.: 1633

Group Art Unit: 2851

Examiner: Fuller, Rodney Evan

Title: LITHOGRAPHIC PROJECTION APPARATUS, DEVICE MANUFACTURING  
METHOD, DEVICE MANUFACTURED THEREBY AND GAS COMPOSITION

June 30, 2003

\* \* \* \* \*

**AMENDMENT**

Hon. Commissioner of Patents  
Washington, D.C. 20231

Sir:

In response to the Office Action dated January 30, 2003, please enter the following  
amendments and remarks:

**IN THE SPECIFICATION:**

Please amend paragraph [0034] as follows:

The radiation system comprises a source LA (*e.g.* an Hg lamp or an excimer laser) that produces a beam of radiation. This beam is fed into an illumination system (illuminator) IL, either directly or after being passed through conditioning means, such as a beam expander Ex, for example. The illuminator IL comprises adjusting means for setting the outer and/or inner radial extent (commonly referred to as  $\sigma$ -outer and  $\sigma$ -inner, respectively) of the intensity distribution in the beam. In addition, it will generally comprise various other components, such as an integrator IN and a condenser CO. In this way, the beam PB impinging on the mask MA has a desired uniformity and intensity distribution in its cross-section.

**Please see the attached Appendix for the changes made to effect the above paragraphs.**

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